

Supporting Information For

Carrier Control of MoS₂ Nanoflakes by Functional Self-Assembled Monolayers

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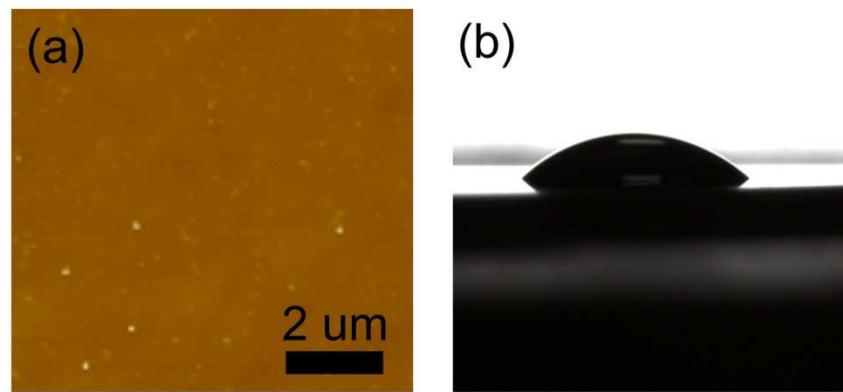


Figure S1. (a) AFM topography of Si substrate with a 300 nm thick oxide layer. The roughness of SiO_2 substrate is 0.46 nm. (b) The water contact angle of the pristine Si substrate treated by piranha solution.

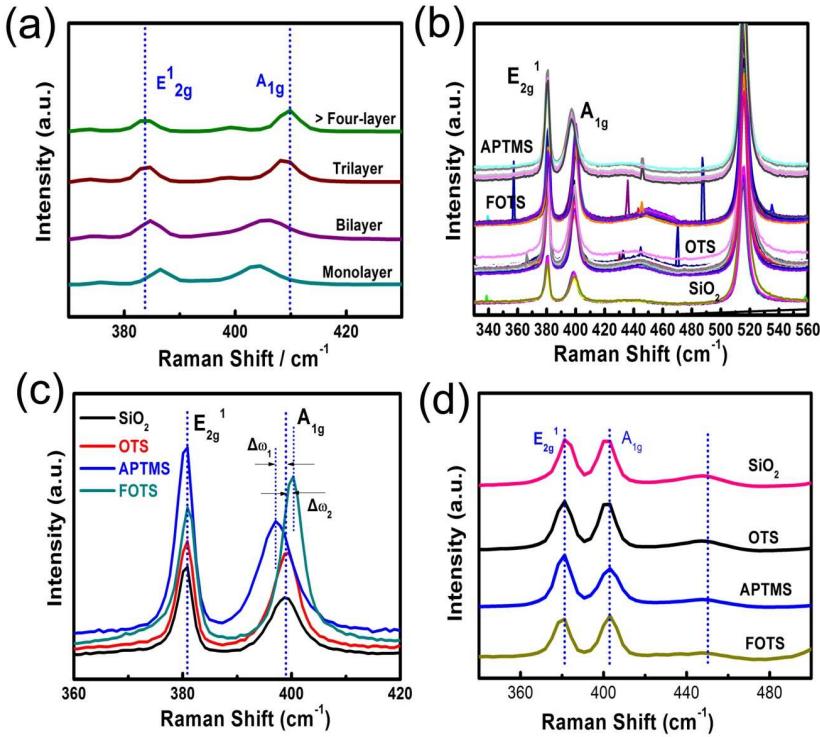


Figure S2. (a) Raman spectra of MoS₂ nanoflakes on pristine SiO₂ substrates. (b) Raman spectra of monolayer MoS₂ on the pristine and SAMs-modified substrates. The Raman mode of Si is not dependent on SAMs molecules. Therefore, the relative Raman shifts of E_{2g}¹ and A_{1g} mode are calculated using Raman mode of Si as a reference. (c) The typical Raman spectra of monolayer MoS₂ on the pristine and SAMs-modified substrates according to Figure S2a. (d) The typical Raman spectra of pristine and SAMs-modified bilayer MoS₂ nanoflakes.

Figure S2a presents the Raman spectra of pristine MoS₂ nanoflakes. For monolayer MoS₂, there are two prominent Raman modes: out-of-plane mode E_{2g}¹ and in-plane mode A_{1g}, and the peaks distance is about 18.7 cm⁻¹. E_{2g}¹ presents redshift with increasing thicknesses of MoS₂ nanoflakes, while A_{1g} shows blueshift. From Figure S2d, the positions and shapes of E_{2g}¹ and A_{1g} modes are almost independent on SAMs molecules. The relative strong interlayer screening

effect and the weaker doping for bilayer MoS₂ lead to the unnoticeable variation of Raman modes by Raman spectroscopy.

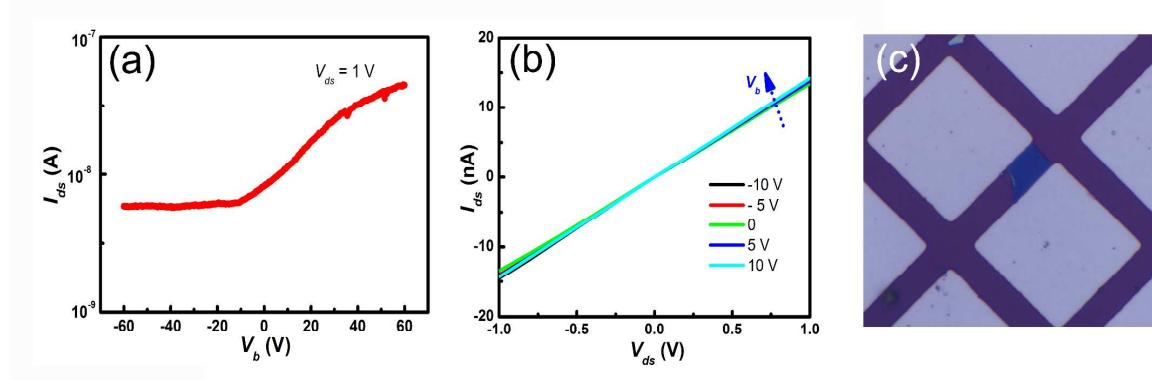


Figure S3. The transfer (a) and (b) output characteristics of FOTS- modified tri-layer MoS₂ device. The ON-state current and ON/OFF ratio are lowest, and the source-drain current (I_{ds}) does not vary significantly when the different gate voltage (V_b) is applied. (c) The typical configuration of the devices in our work. The channel length is 6 μ m. The bilayer MoS₂ presents purple, and the size is relative large for the device fabrication.

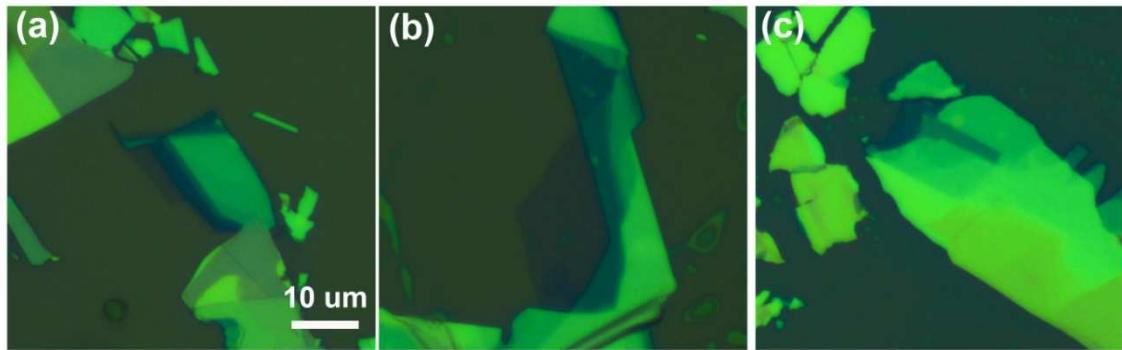


Figure S4. Optical images of MoS₂ nanoflakes on (a) pristine, (b) OTS-modified, (c) FOTS-modified substrates, respectively.

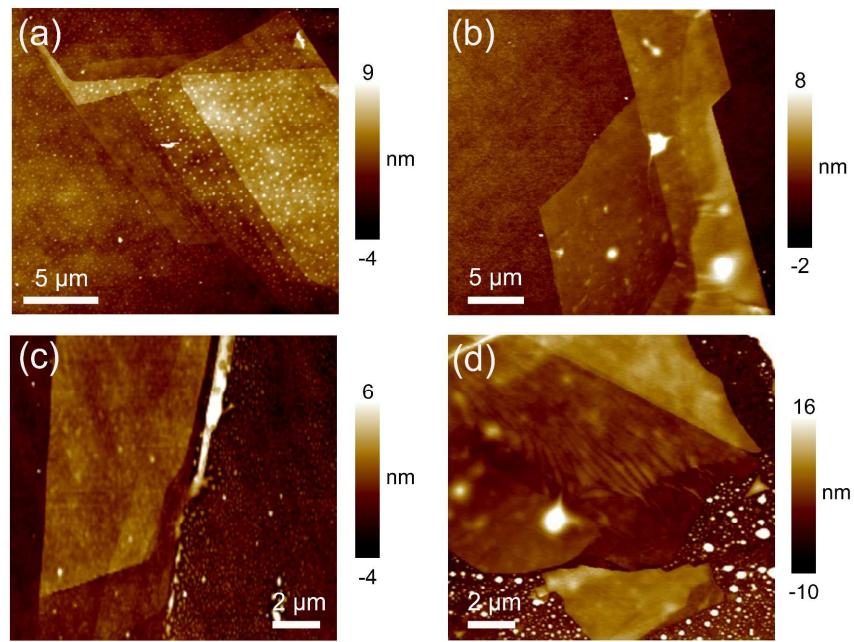


Figure S5. AFM images of MoS₂ nanoflakes on (a) pristine, (b) OTS-modified, (c) APTMS-modified, and (d) FOTS-modified substrates, respectively.

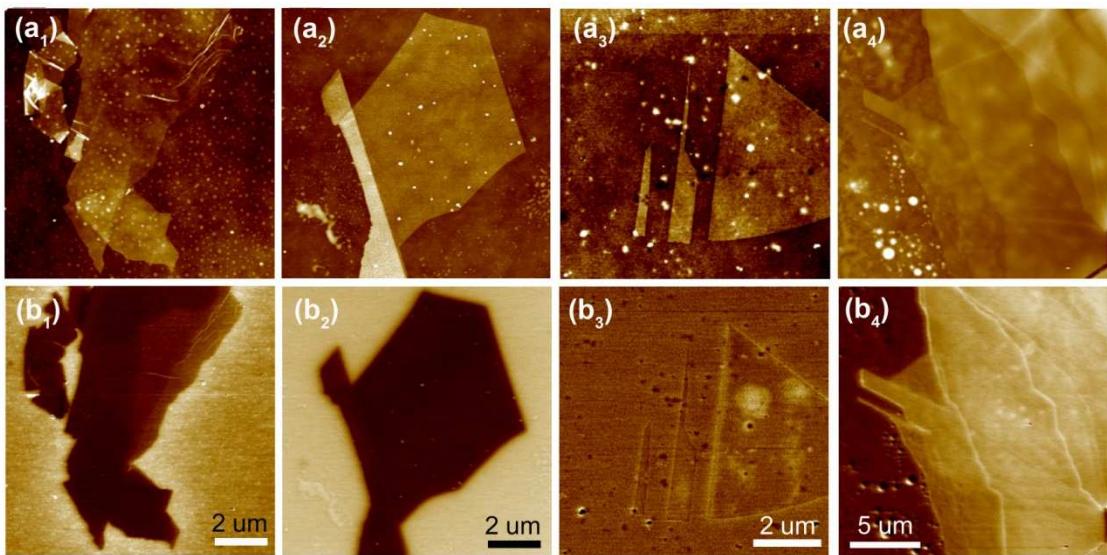


Figure S6. AFM topographies and surface potential maps of MoS₂ nanoflakes on the pristine and SAMs-modified SiO₂ substrates. (a₁-d₁) The topographies of MoS₂ nanoflakes on SiO₂, OTS, APTMS and FOTS. (a₂-d₂) The corresponding surface potential maps of MoS₂ nanoflakes shown in a₁-d₁.

In Figure S6, the surface potential of MoS₂ nanoflakes on pristine substrate decreases with the number of layer (shown in a₁ and b₁); the contact potential difference between tri-layer MoS₂ and 6-layer MoS₂ nanoflakes (shown in a₂ and b₂) presents no significant change; bilayer MoS₂ on ATPMS-modified substrate have the similar surface potential to APTMS-SAM (shown in a₃ and b₃). The surface potential of MoS₂ nanoflakes on FOTS-modified substrates increases with the number of layer (shown in a₄ and b₄).

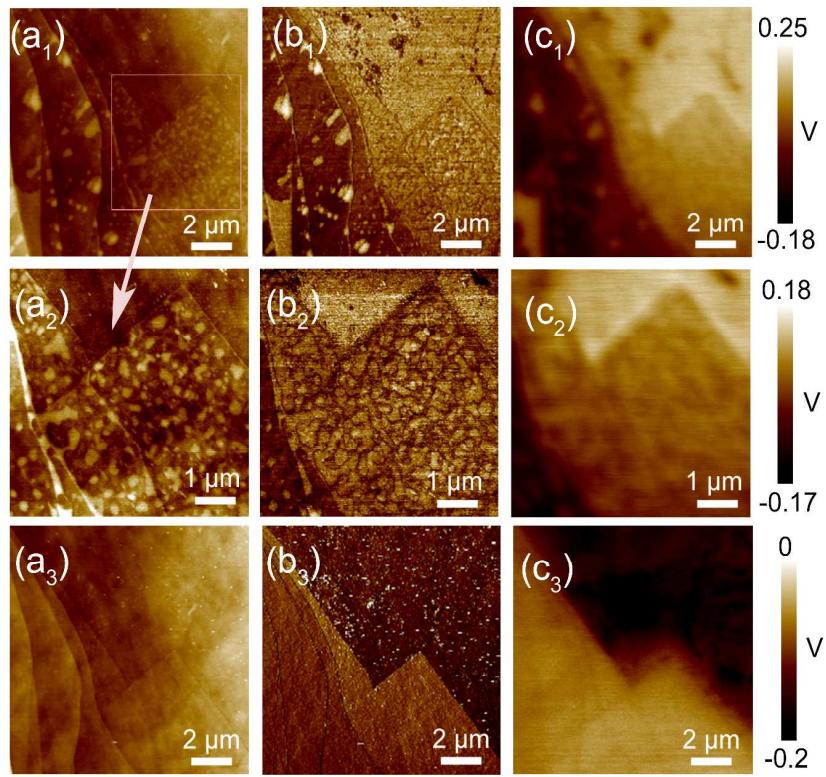


Figure S7. The topographies, phases and surface potential maps of the pristine and annealed MoS₂ nanoflakes on the pristine SiO₂ substrates.

The structure of MoS₂ can not be destroyed since the annealing temperature (230 °C) is much lower than the phase transition temperature. As we have verified below (lines 101-107, Page S9), the sharp phase contrast in Figure S7b₁ indicates the formed water layers upon the pristine MoS₂ nanoflakes, while the trivial phase contrast in Figure S7b₂ (the enlarged area in Figure S7a₁) indicates the formed water layers underneath MoS₂ nanoflakes. Before annealing, the obvious surface potential difference can be observed, and the surface potential decreases by increasing the thickness. After annealing, the water layers upon or underneath MoS₂ nanoflakes are eliminated (as shown in Figure S7b₃, phase image), and the surface potential of annealed MoS₂ nanoflakes is lower than that of the pristine samples (For monolayer MoS₂, the surface

potential decreases by 0.12 ± 0.03 V after annealing). Meanwhile, it should be noting that the interlayer screening effect seems to be not obvious after annealing, as shown in Figure S7c₃.

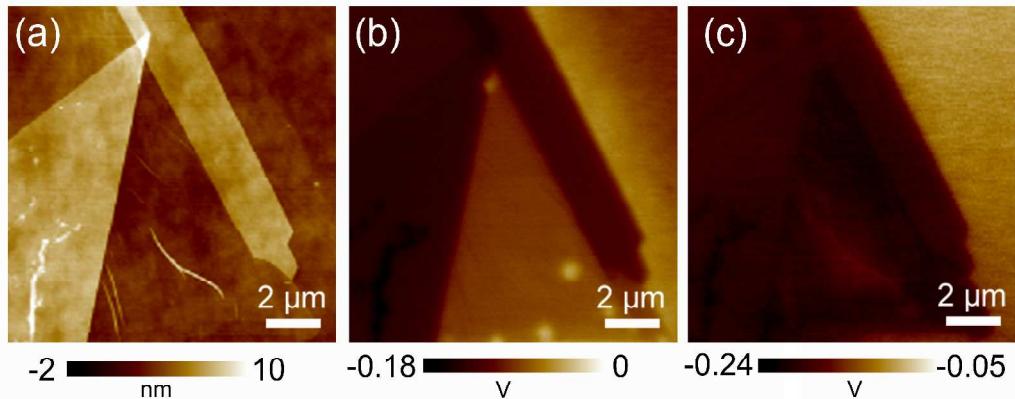


Figure S8. The topographies, phase and surface potential maps of the pristine and annealed MoS₂ nanoflakes on OTS-modified SiO₂ substrates.

OTS has strong hydrophobicity, and the water layer upon or underneath MoS₂ nanoflakes is not observed. MoS₂ nanoflakes modified by OTS are annealed at 140 °C for 4 h. The lower annealing temperature is applied to avoid the destruction of OTS. Compared with the pristine samples (shown in Figure S8b), the surface potential of annealed MoS₂ shown in Figure S8c also lowers (For monolayer MoS₂, the surface potential decreases by 0.10 ± 0.02 V after annealing) and the weak interlayer screening effect of annealed MoS₂ nanoflakes is also observed.

From Figures S7, S8 and the corresponding explanations, we demonstrate the effects of the water molecules on the surface potential of MoS₂ nanoflakes. Before annealing, the distinct interlayer screening effect is observed, while after annealing the interlayer screening effect seems to be weak. For monolayer MoS₂, the surface potential decreases by about 0.10-0.12 V. The results demonstrate that the water molecules indeed shield the actual surface potential of MoS₂ nanoflakes, and the effect of water molecules is complicated, and need to be analyzed in depth.

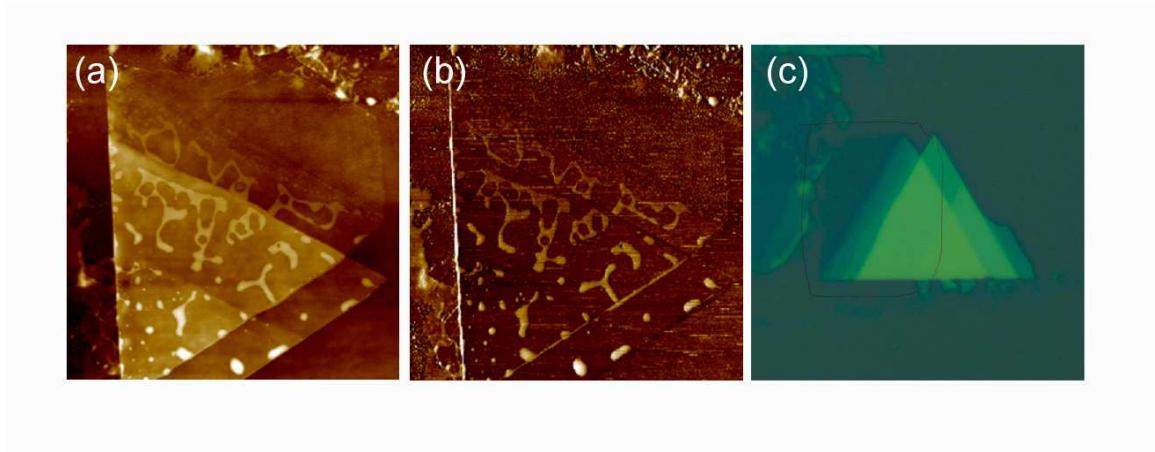


Figure S9. AFM topography (a) and the corresponding phase image (b) MoS₂ nanoflakes on the pristine SiO₂ substrate. (c) Optical images of MoS₂ nanoflakes on pristine SiO₂ substrates.

From the phase image (Figure S9b), the significant phase difference is observed between water layers and MoS₂ nanoflakes, reflecting the difference in surface potential. According to the relevant research about graphene, if the water layers exist underneath graphene, the phase difference will be trivial.^{1,2} However, the large phase difference indicates that the AFM tip is interacting with the different surface (MoS₂ and water layers in our experiments), and the water layers absorb upon the MoS₂ nanoflakes. According to the AFM topography (Figure S9a), the height of the water layers is about 3 nm.

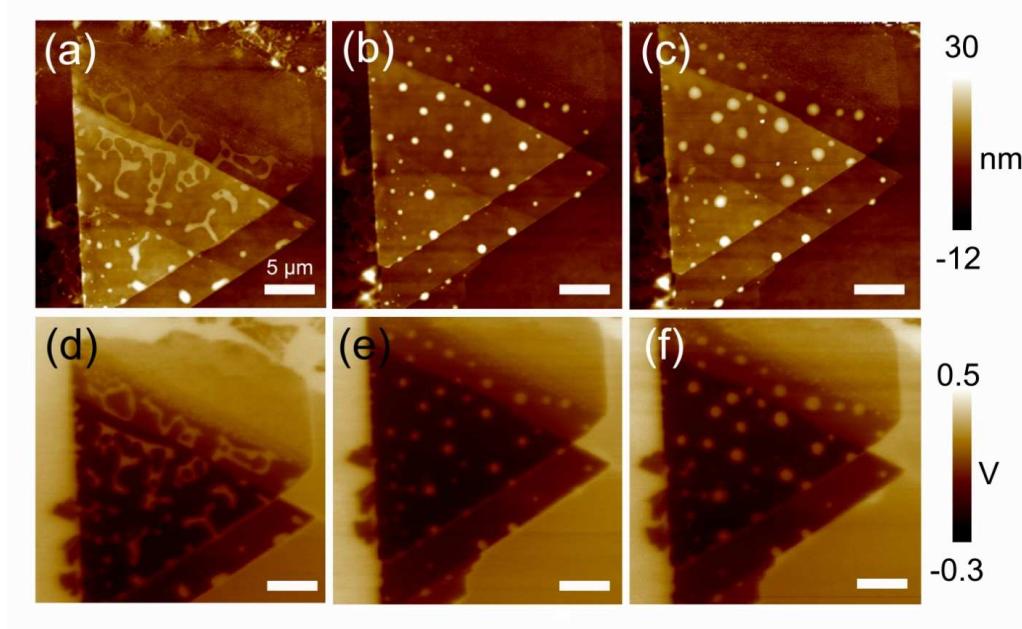


Figure S10. The topographies and the corresponding surface potential maps of MoS₂ nanoflakes on the pristine SiO₂ substrates. (a), (d) at room atmosphere 45%; (b), (e) 61%; (c), (f) 80 %.

By increasing the humidity, the height of the formed water layers increases from 3 nm to 21 nm. From Figure S10d-f, the surface potential of MoS₂ with water layers is lower than that of MoS₂ without water layers, verifying that the formed water layers shield the actual surface potential of MoS₂ nanoflakes.^{3,4} It should be noted that the other areas of MoS₂ nanoflakes, which are not covered with the formed water layers, still absorbs external water molecules. However, the surface potential of MoS₂ nanoflakes without water layers keeps nearly constant when the humidity increases from 45% to 80%.

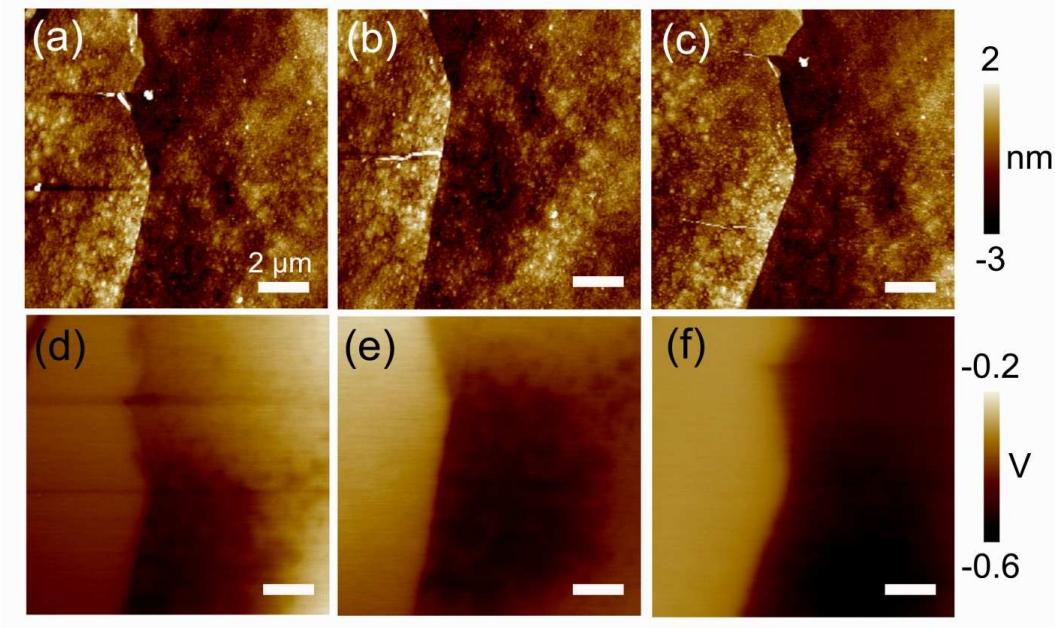


Figure S11. AFM topographies and the corresponding surface potential maps of MoS₂ nanoflakes on FOTS-modified monolayer MoS₂ at different relative humidity.(a), (d) at room atmosphere 45%; (b), (e) 65%; (c), (f) 78 %. The scale bars are all 2 μ m.

The annealing experiments have demonstrated that the absorbed water molecules indeed have significant effects on the carrier distribution of MoS₂ nanoflakes. According to Figure S11, when the humidity increased from 45% to 78%, the surface potential of monolayer MoS₂ had little variation, indicating that the effect of the externally absorbed water molecules on the carrier distribution of MoS₂ is almost constant.

According to humidity and annealing experiments, KFM seems to be not the most reliable method to evaluate the interfacial charge transfer due to the significant effect of external atmosphere. The absorbed water molecules indeed shield the actual surface potential of MoS₂. Compared to the pristine MoS₂, the interlayer screening effect of annealed MoS₂ seems to become weaker. For monolayer MoS₂, the surface potential decreases by about 0.08-0.12 V.

Therefore, by eliminating the contribution of the absorbed water layers or molecules, we think that the actual Fermi level shift of monolayer MoS₂ is about 0.45-0.47 eV.

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